



Docket No.: ATMI-478
Customer ID No.: 25559

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:

Applicants: Chongying Xu, et al.

Serial No.: 09/551,018

Date Filed: April 18, 2000

Title: SILICON REAGENTS AND LOW TEMPERATURE CVD METHOD OF
FORMING SILICON-CONTAINING GATE DIELECTRIC MATERIALS
USING SAME

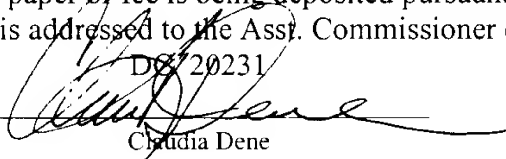
)
)
) Examiner: C. Toomer
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) Group Art Unit: 1714
)
)

CERTIFICATE OF MAILING

I hereby certify that this paper or fee is being deposited pursuant to 37 CFR 1.8
on the date indicated below and is addressed to the Asst. Commissioner of Patents, Washington,

D8720231


Claudia Dene

August 26, 2002

Date

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SEP 4 - 2002
TC 1700

PETITION UNDER 37 CFR 1.136 FOR ONE (1) MONTH EXTENSION OF TIME,
IN RESPECT OF SUBMISSION OF RESPONSE TO THE APRIL 26, 2002 OFFICE ACTION

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Petition hereby is made under the provisions of 37 CFR 1.136 for a one (1) month
extension of the time for submission of Amendment and Response in response to the April 26,
2002, which set a three (3) month term for response, expiring July 26, 2002.

With the entry of this Petition, the response term is extended to expire on August 26, 2002.

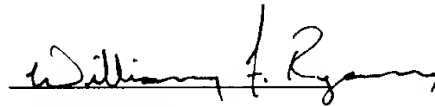
Please charge deposit account no. 50-0860 in the amount of \$110.00, as the fee specified in 37 CFR 1.17 for this Petition for Extension of Time.

The Amendment/Response is concurrently submitted herewith.

Any deficiency or over payment should be charged or credited to Deposit Account No. 50-0860.

Date: August ²¹~~26~~, 2002

Respectfully submitted,



William Ryann
Registration No. 44,313
Attorney for Applicants

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